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# **Materials Science of High-K Dielectric Stacks-From Fundamentals to Technology**

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## TABLE OF CONTENTS

<b>Oxygen Vacancies in Amorphous HfO<sub>2</sub> and SiO<sub>2</sub></b> .....	1
<i>C. Kaneta, T. Yamasaki</i>	
<b>Work Function Tuning of Mo<sub>x</sub>Si<sub>y</sub>N<sub>z</sub> metal gate electrode for Advanced CMOS Technology</b> .....	8
<i>P. Patel, D.A. Buchanan, R.M. Wallace</i>	
<b>Atomic Layer Deposition of HfO<sub>2</sub> Thin Films on Si and GaAs Substrates</b> .....	13
<i>J.C. Hackley, J.D. Demaree, T. Gougousi</i>	
<b>Physical Origin of Colossal Dielectric Constant in CaCu<sub>3</sub>Ti<sub>4</sub>O<sub>12</sub> Thin Film by Pulsed Laser Deposition</b> .....	19
<i>G. Deng, T. Yamada, P. Murali</i>	
<b>Thermally-Stable High Effective Work Function TaCN and Ta<sub>2</sub>N Films for pMOS Metal Gate Applications</b> .....	25
<i>C. Adelman, P. Lehnen, L.A. Ragnarsson, T. Conard, A. Franquet, V.S. Chang, E. Rohr, J. Meersschaut, O. Boissiere, C. Lohe, T. Schram, S. Van Elshocht, S. De Gendt</i>	
<b>In Pursuit of "Super" High-k Ternary Oxides: Aqueous CSD and Material Properties</b> .....	31
<i>A. Hardy, S. Van Elshocht, J. D'Haen, S. De Gendt, M.K. Van Bael, M. Heyns, M. D'Olieslaeger, J. Mullens</i>	
<b>Strategies for CMOS Low Equivalent Oxide Thickness Achievement with High-k Oxides Grown on Si(001) by MBE</b> .....	37
<i>L. Becerra, C. Merckling, N. Baboux, M. El-Kazzi, G. Saint-Girons, B. Vilquin, C. Plossu, G. Hollinger</i>	
<b>Electrical Properties of Thermally Grown HfO<sub>2</sub> and HfO<sub>2</sub>/TiO<sub>2</sub>/HfO<sub>2</sub> MIM Capacitors Fabricated on SiO<sub>2</sub>/Si Substrate and HfO<sub>2</sub> MIM Capacitors Fabricated on Sapphire</b> .....	43
<i>B. Miao, R. Mahapatra, N. Wright, A. Horsfall</i>	
<b>Effect of GaAs Surface Treatments on Lanthanum Silicate High-K Dielectric Gate Stack Properties</b> .....	49
<i>D.J. Lichtenwalner, R. Suri, V. Misra</i>	
<b>Physico-chemical Characterization of Thin Oxide Films: Difficulties and Solutions</b> .....	55
<i>T. Conard, W. Vandervorst</i>	
<b>The Study of Hafnium Silicate by Various Nitrogen Gas Annealing Treatment</b> .....	68
<i>D.C. Suh, K.B. Chung, M. Cho, Y.D. Cho, D. Ko</i>	
<b>Author Index</b>	